Editorial

This issue contains a selection of papers presented at symposium R of the 2009 Spring Meeting of the European Materials Research Society, devoted to “X-ray techniques for Advanced Materials, Nanostructures and Thin Films: from Laboratory Sources to Synchrotron Radiation”; the meeting was held in Strasbourg (France) from June 8th to June 12th.

The papers highlight recent developments in the application of X-ray and Synchrotron Radiation techniques to the study of advanced materials. The symposium was very well attended, with 175 abstracts submitted. The program included 14 invited talks and 39 oral contributions; results which could not be presented as oral contributions were discussed during two lively poster sessions. A full morning was dedicated to a joint session with symposium B on X-ray studies of photovoltaic materials.

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